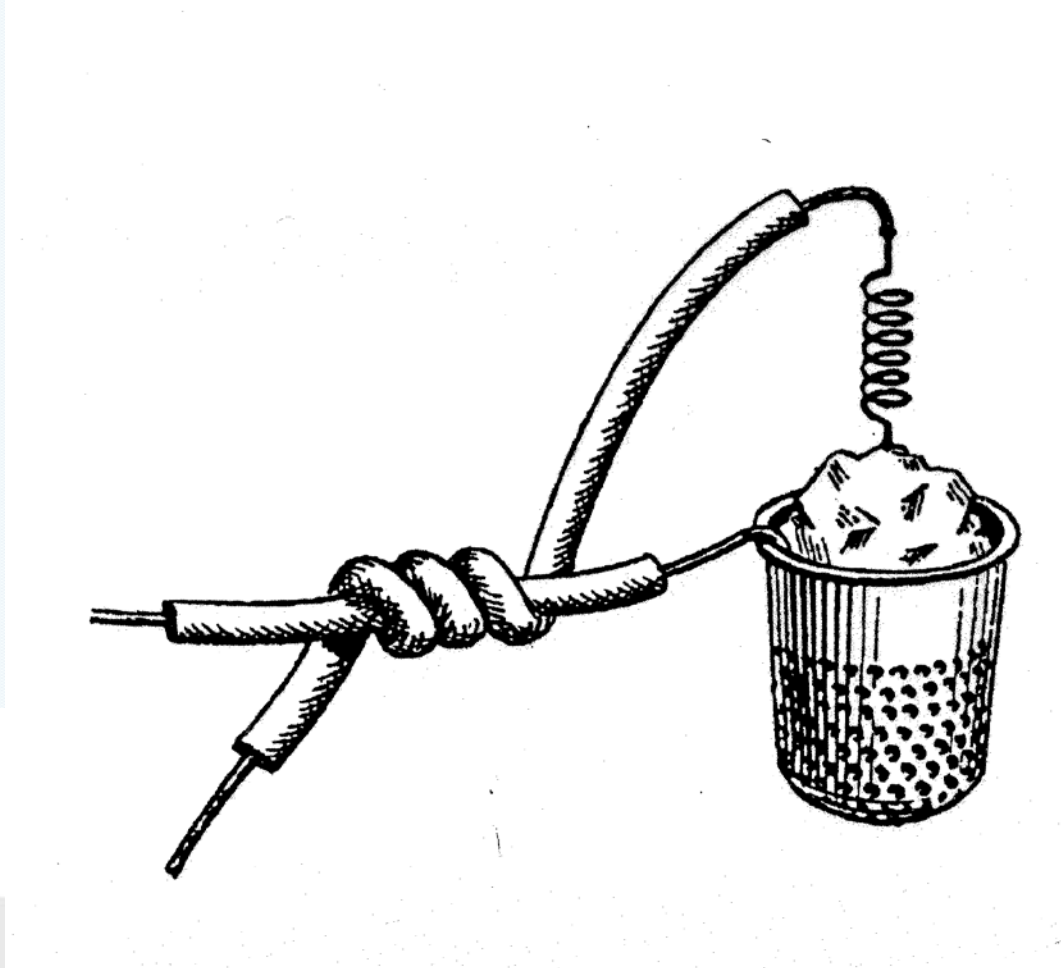


Introduction to Semiconductor



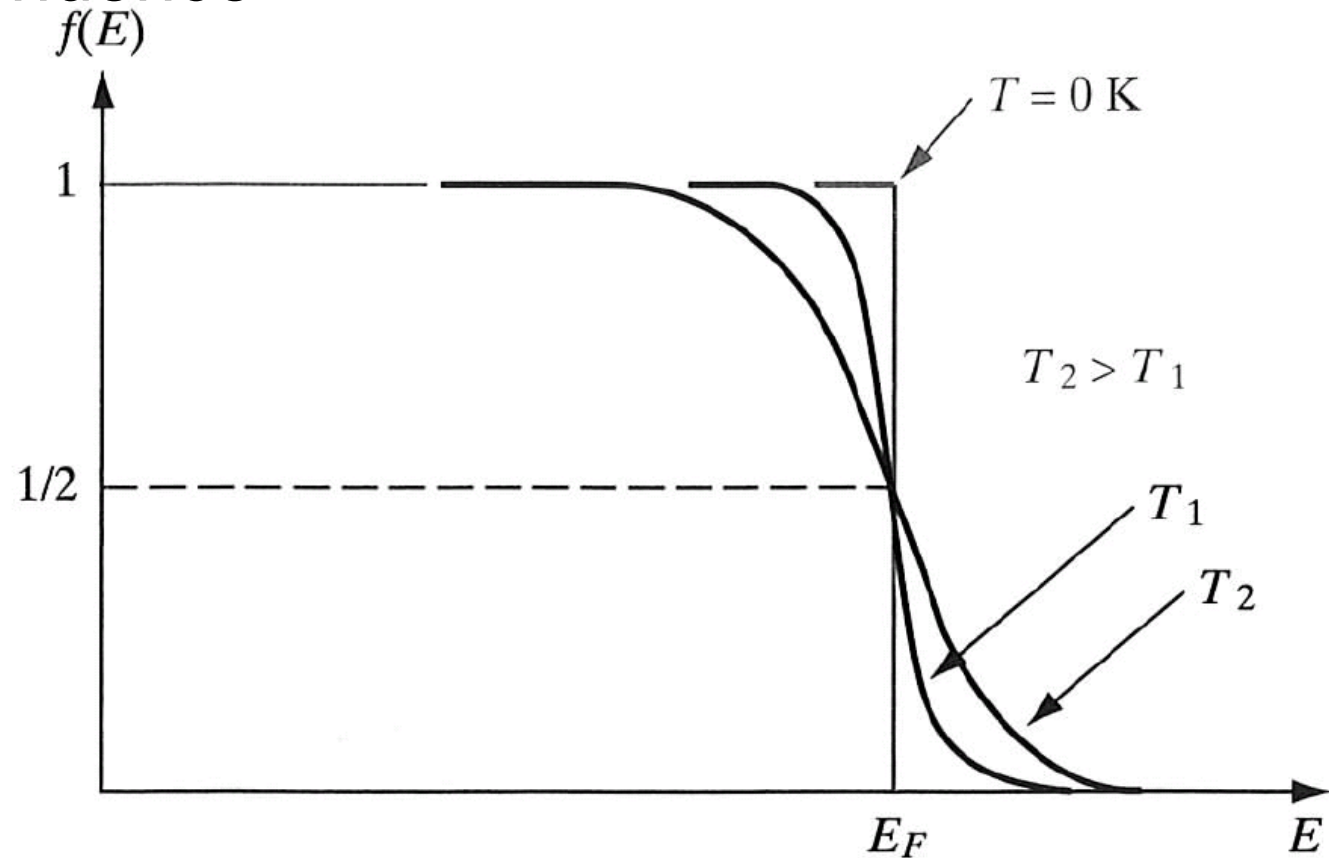
Outline

3 Energy Bands and Charge Carriers in Semiconductors

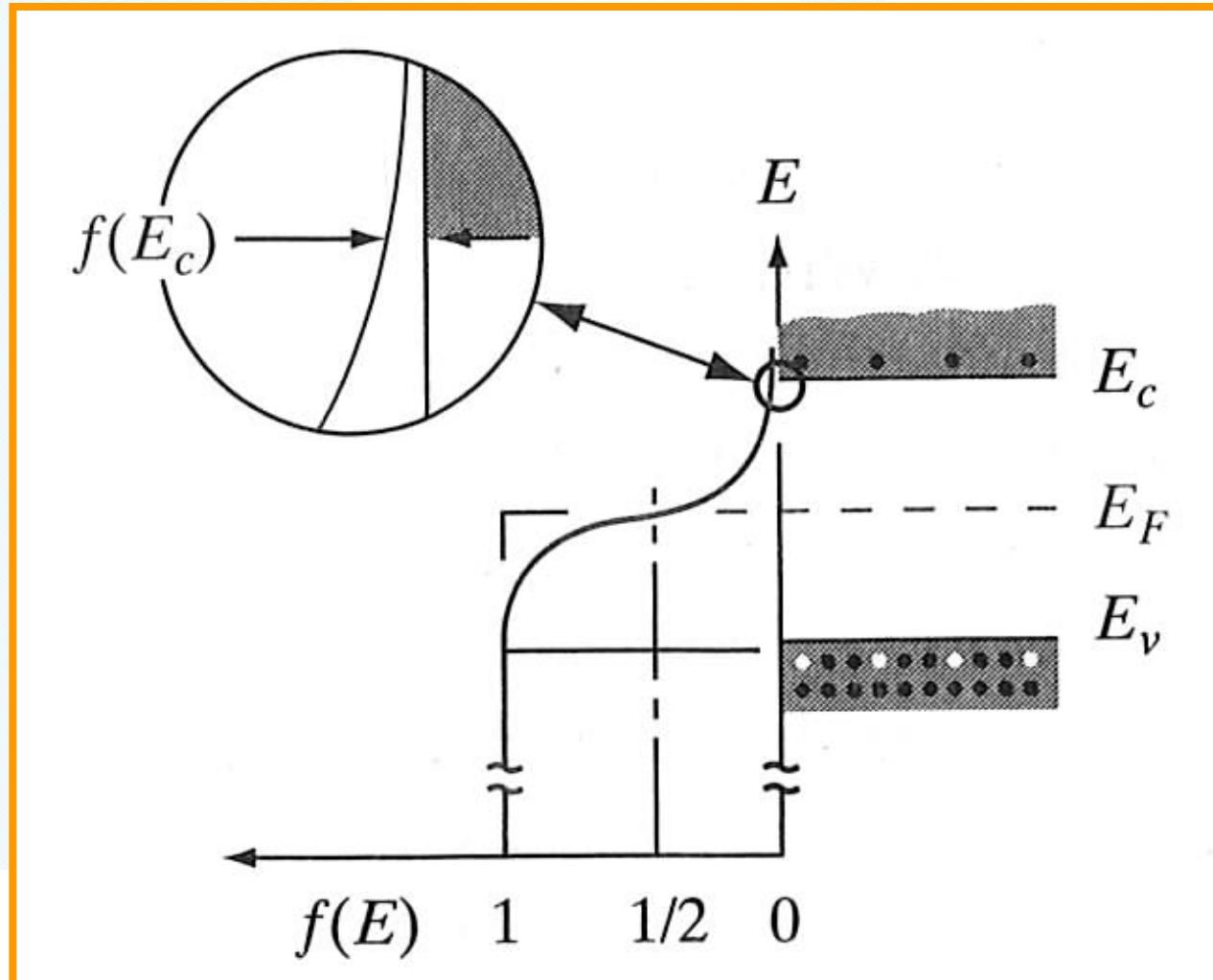


Charge Carriers concentration

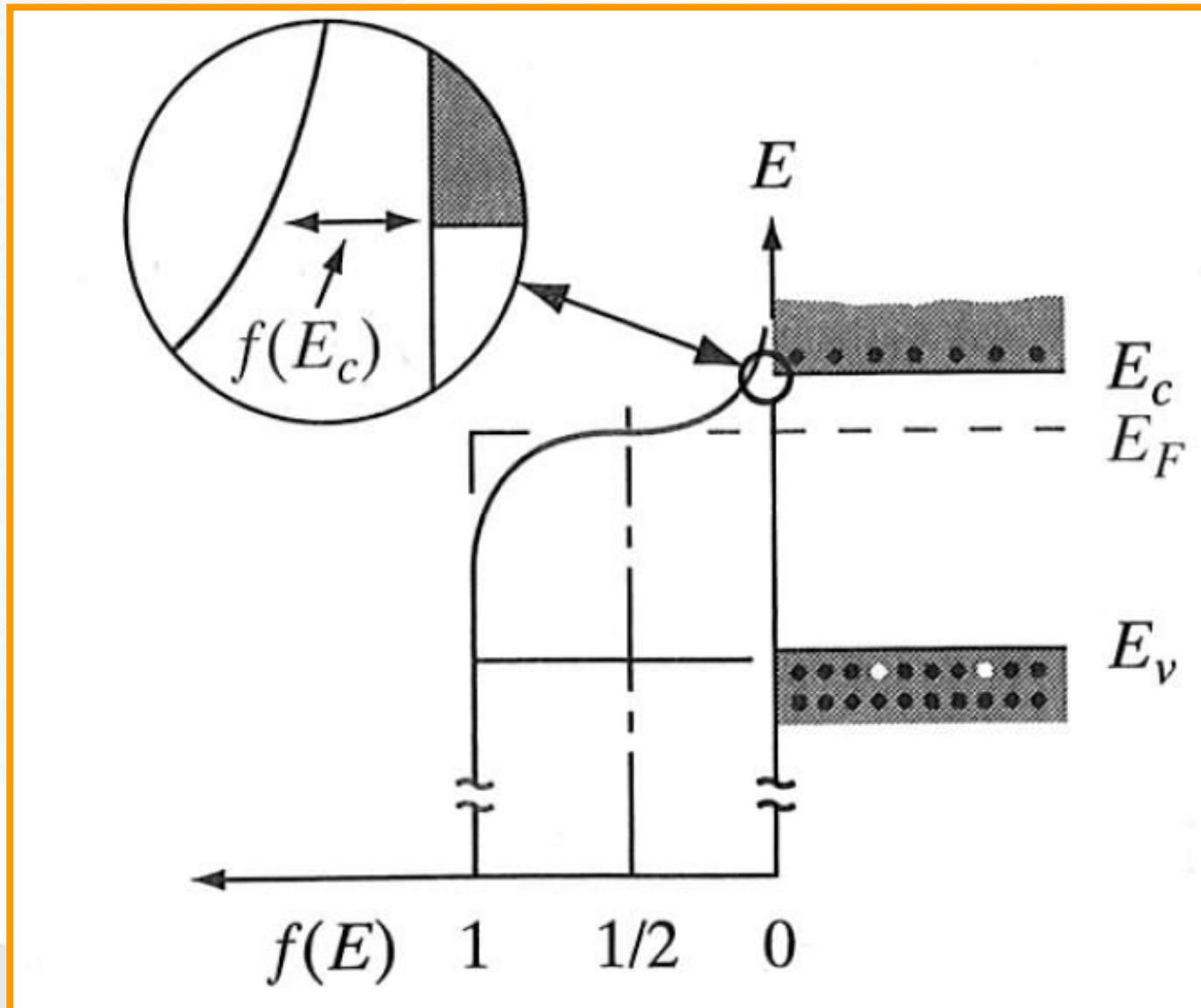
Temperature dependence



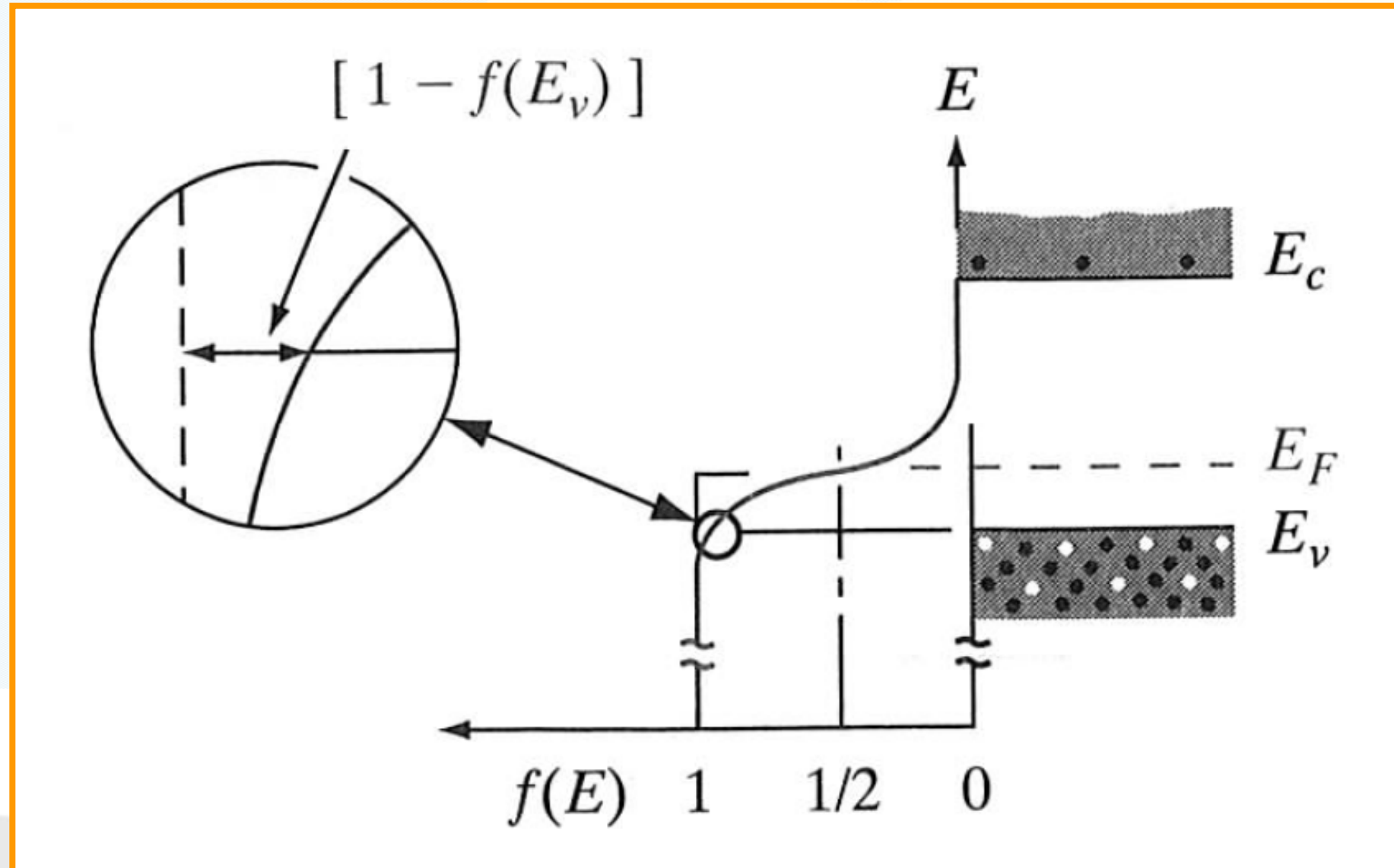
The Fermi distribution for intrinsic (undoped) semiconductor



The Fermi distribution for n-doped semiconductor



The Fermi distribution for p-doped semiconductor



Electron and hole concentration in equilibrium

For electrons applies

$$n_0 = \int_{E_c}^{\infty} f(E)N(E)dE$$

Where $N(E)dE$ is the density of states in cm^{-3} within dE

Integrations gives (appendix IV)

$$n_0 = N_c f(E_c)$$

Subscript denotes Equilibrium



Electron concentration in equilibrium

$$N_c = 2 \left(\frac{2\pi m_n^* kT}{h^2} \right)^{3/2}$$

Effective density of states

$$f(E_c) = \frac{1}{1 + e^{(E_c - E_F)/kT}} \simeq e^{-(E_c - E_F)/kT}$$

$$E_c - E_f > kT$$

$$kT = 0.0259 \text{ eV RT}$$

$$n_0 = N_c e^{-(E_c - E_F)/kT}$$



Hole concentration in equilibrium

$$N_v = 2 \left(\frac{2\pi m_p^* kT}{h^2} \right)^{3/2}$$

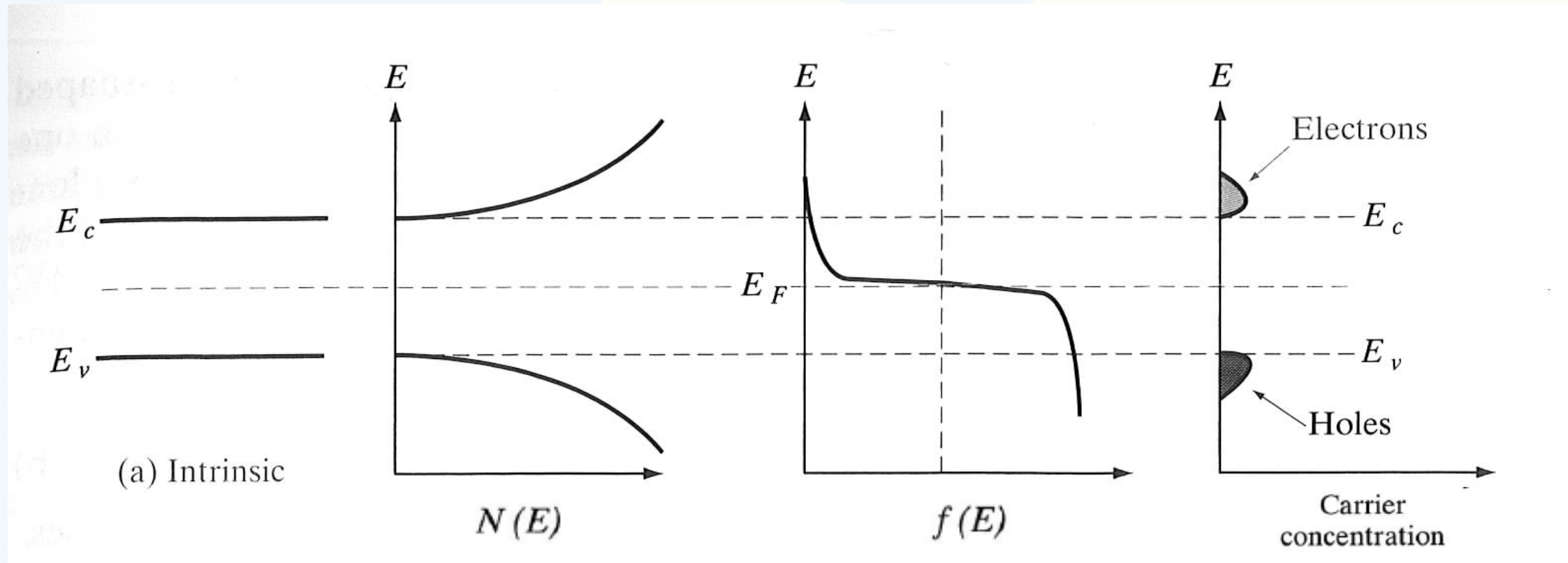
Effective density of states

$$1 - f(E_v) = 1 - \frac{1}{1 + e^{(E_v - E_F)/kT}} \simeq e^{-(E_F - E_v)/kT}$$

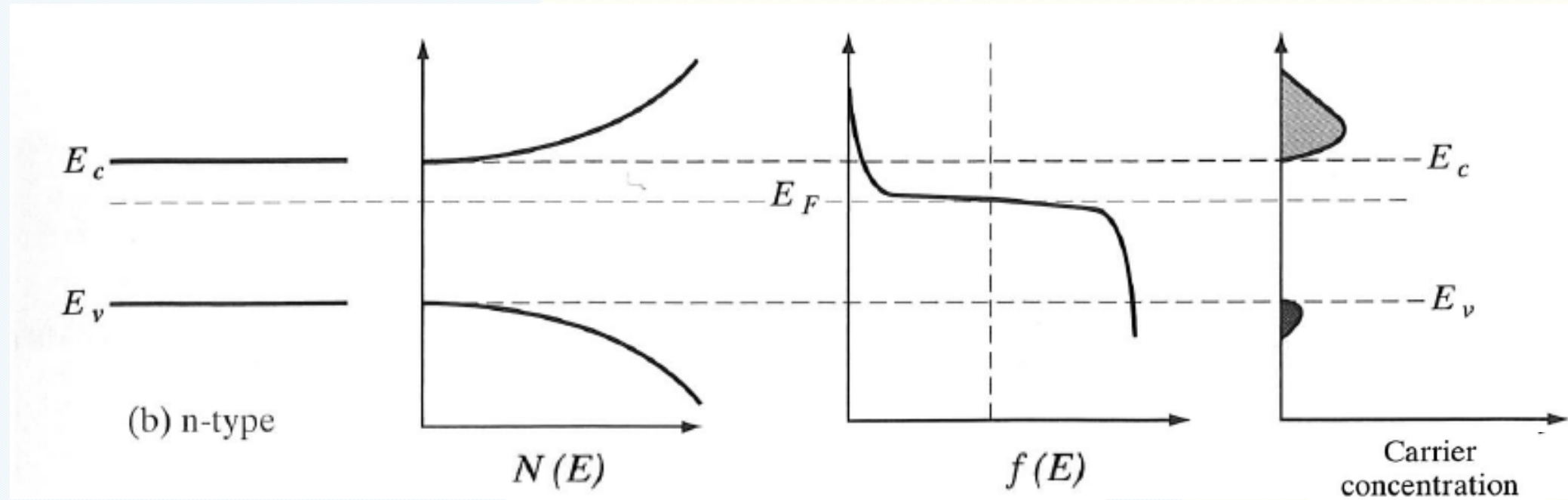
$$E_F - E_v > kT$$

$$p_0 = N_v e^{-(E_F - E_v)/kT}$$

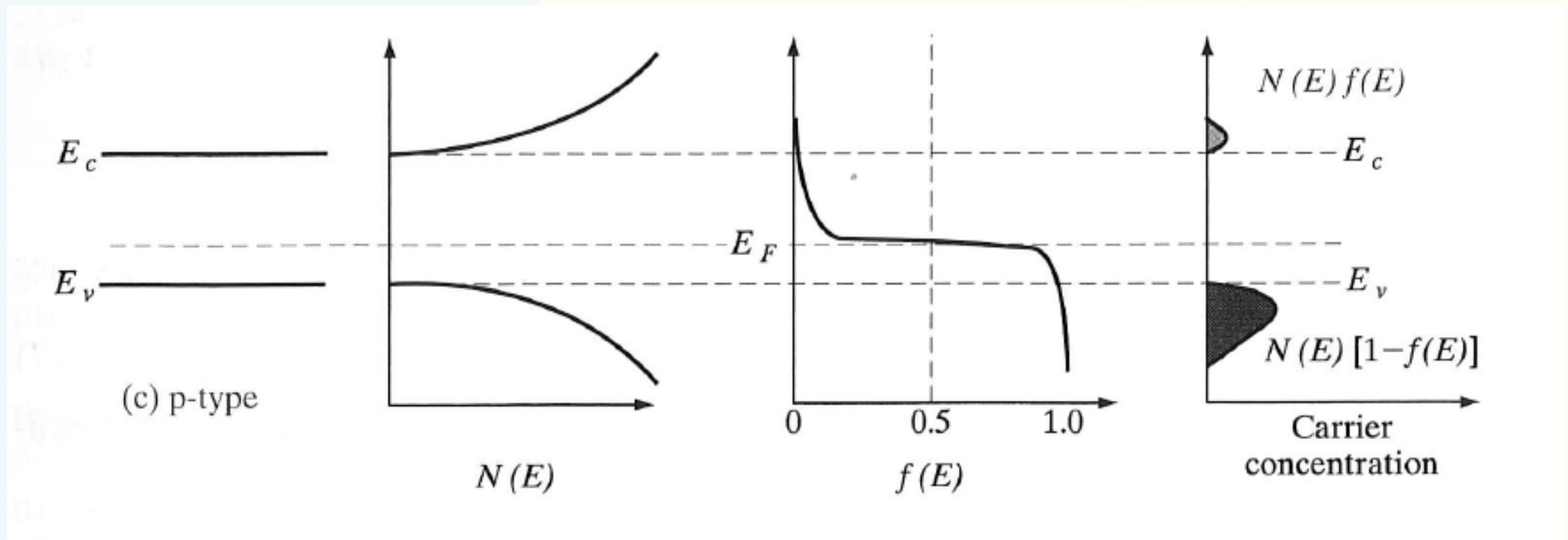
Band-diagram (undoped)



Band-diagram n-type



Band-diagram p-type



Effective mass

- Effective mass when calculating the density of states, silicon

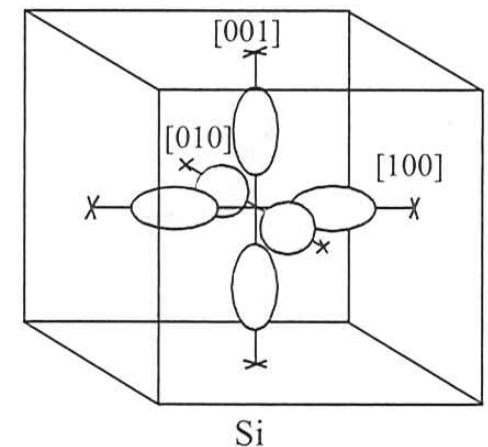
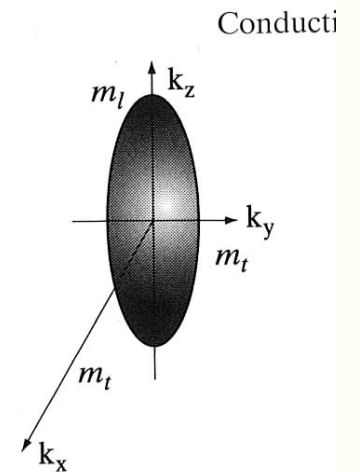
$$(m_n^*)^{3/2} = 6(m_l m_t^2)^{1/2}$$

6 Energy surfaces
in silicon

$$m_n^* = 1.1m_0 \quad m_l = 0.98m_0 \quad m_t = 0.19m_0$$

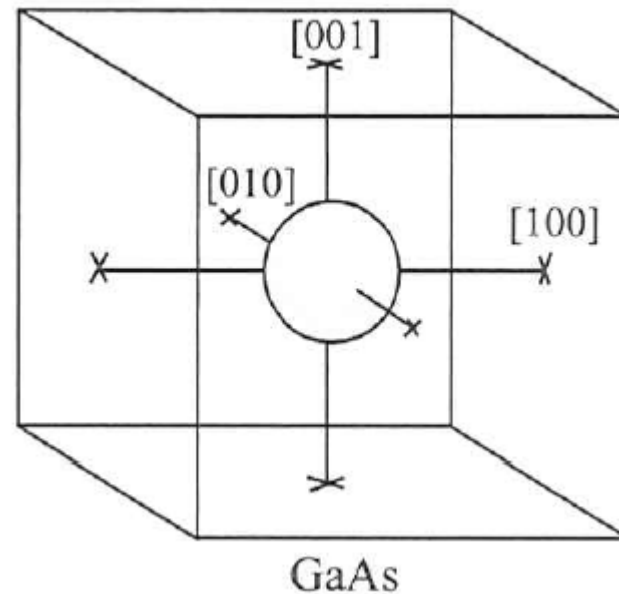
- Effective mass when calculating the conductivity (movement of charge), silicon

$$\frac{1}{m_n^*} = \frac{1}{3} \left(\frac{1}{m_l} + \frac{2}{m_t} \right) \quad m_n^* = 0.26m_0$$



Effective mass

For GaAs, where the conduction band is spherically is the effective mass of the electrons in the calculation of the density of states and conductivity as $(0.067m_0)$



Effective mass table

		E_g (eV)	μ_n (cm ² /V-s)	μ_p (cm ² /V-s)	m_n^*/m_0 (m_l, m_t)	m_p^*/m_0 (m_{lh}, m_{hh})	a (Å)	ϵ_r	Density (g/cm ³)	Melting point (°C)
Si	(i/D)	1.11	1350	480	0.98, 0.19	0.16, 0.49	5.43	11.8	2.33	1415
Ge	(i/D)	0.67	3900	1900	1.64, 0.082	0.04, 0.28	5.65	16	5.32	936
SiC (α)	(i/W)	2.86	500	—	0.6	1.0	3.08	10.2	3.21	2830
AlP	(i/Z)	2.45	80	—	—	0.2, 0.63	5.46	9.8	2.40	2000
AlAs	(i/Z)	2.16	1200	420	2.0	0.15, 0.76	5.66	10.9	3.60	1740
AlSb	(i/Z)	1.6	200	300	0.12	0.98	6.14	11	4.26	1080
GaP	(i/Z)	2.26	300	150	1.12, 0.22	0.14, 0.79	5.45	11.1	4.13	1467
GaAs	(d/Z)	1.43	8500	400	0.067	0.074, 0.50	5.65	13.2	5.31	1238
GaN	(d/Z, W)	3.4	380	—	0.19	0.60	4.5	12.2	6.1	2530
GaSb	(d/Z)	0.7	5000	1000	0.042	0.06, 0.23	6.09	15.7	5.61	712
InP	(d/Z)	1.35	4000	100	0.077	0.089, 0.85	5.87	12.4	4.79	1070
InAs	(d/Z)	0.36	22600	200	0.023	0.025, 0.41	6.06	14.6	5.67	943
InSb	(d/Z)	0.18	10 ⁵	1700	0.014	0.015, 0.40	6.48	17.7	5.78	525
ZnS	(d/Z, W)	3.6	180	10	0.28	—	5.409	8.9	4.09	1650*
ZnSe	(d/Z)	2.7	600	28	0.14	0.60	5.671	9.2	5.65	1100*
ZnTe	(d/Z)	2.25	530	100	0.18	0.65	6.101	10.4	5.51	1238*
CdS	(d/W, Z)	2.42	250	15	0.21	0.80	4.137	8.9	4.82	1475
CdSe	(d/W)	1.73	800	—	0.13	0.45	4.30	10.2	5.81	1258
CdTe	(d/Z)	1.58	1050	100	0.10	0.37	6.482	10.2	6.20	1098
PbS	(i/H)	0.37	575	200	0.22	0.29	5.936	17.0	7.6	1119
PbSe	(i/H)	0.27	1500	1500	—	—	6.147	23.6	8.73	1081
PbTe	(i/H)	0.29	6000	4000	0.17	0.20	6.452	30	8.16	925

All values at 300 K.

*Vaporizes



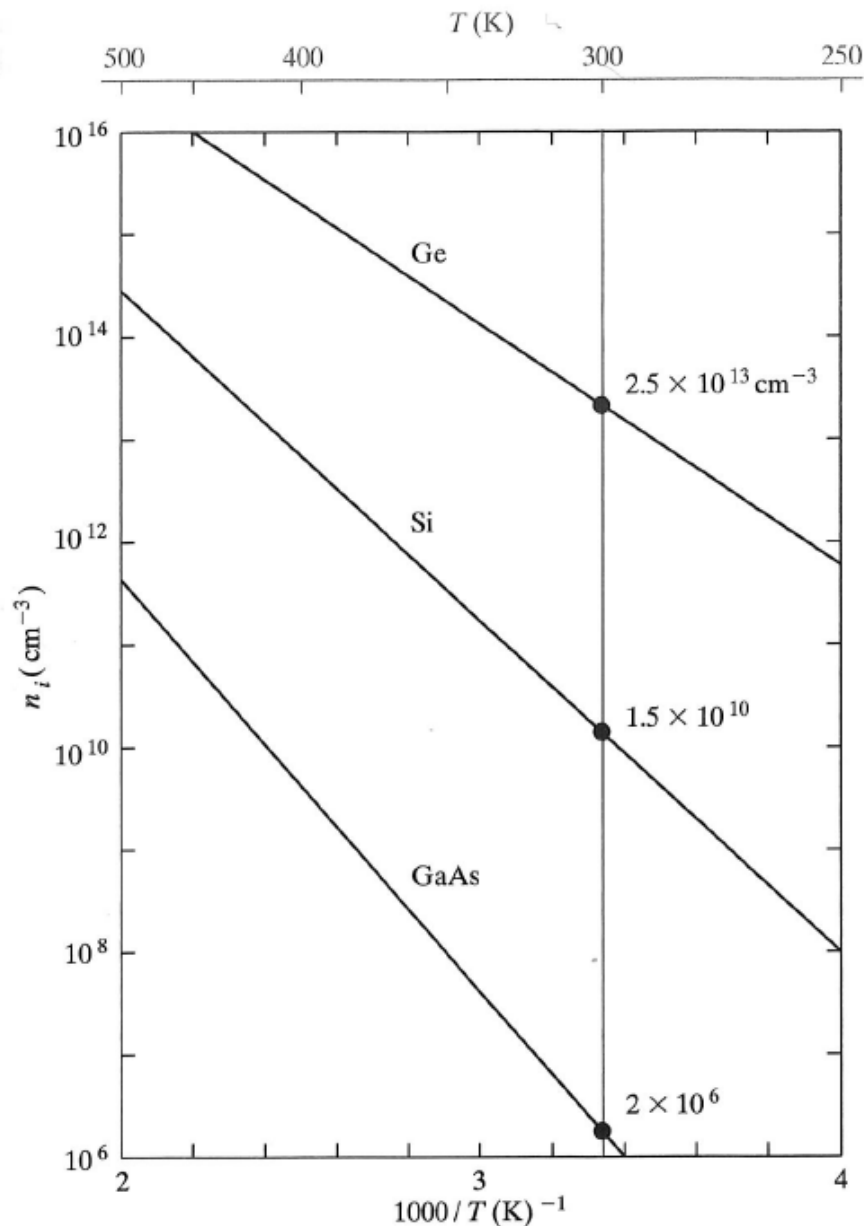
The temperature dependence of the carrier concentration

$$n_i(T) = 2 \left(\frac{2\pi kT}{h^2} \right)^{3/2} (m_n^* m_p^*)^{3/4} e^{-E_g/2kT}$$

Arrenius-plot!

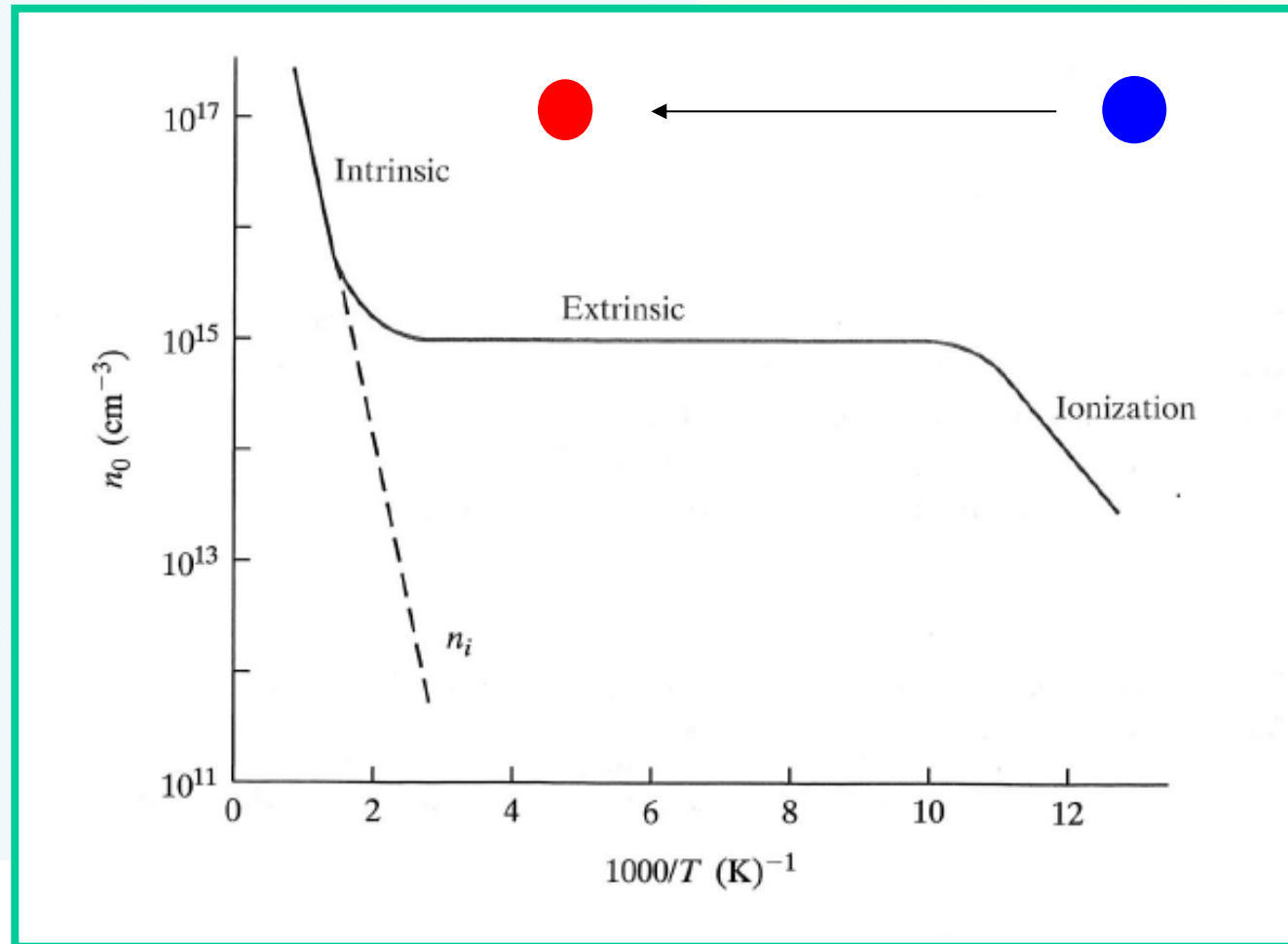
The law of mass action at equilibrium

$$n_0 p_0 = n_i^2$$



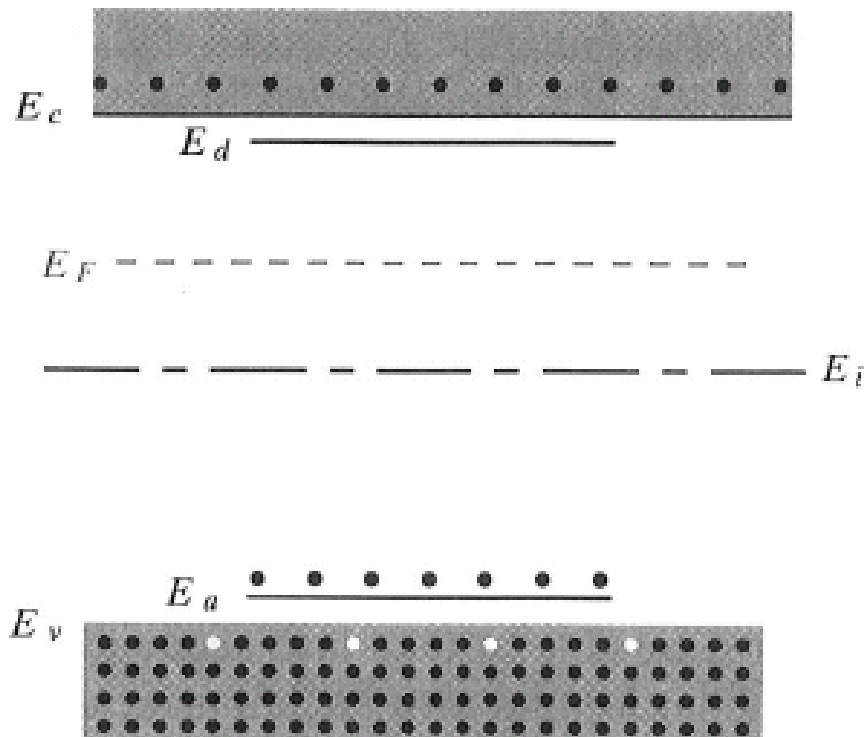
Compensating and charge neutrality

Doped with 10^{15} cm^{-3}
Donators (n-type)



Compensating and charge neutrality

$$N_d > N_a$$



$$p_0 + N_d^+ = n_0 + N_a^-$$

$$n_0 = p_0 + (N_d^+ - N_a^-)$$

$$N_d = N_a$$

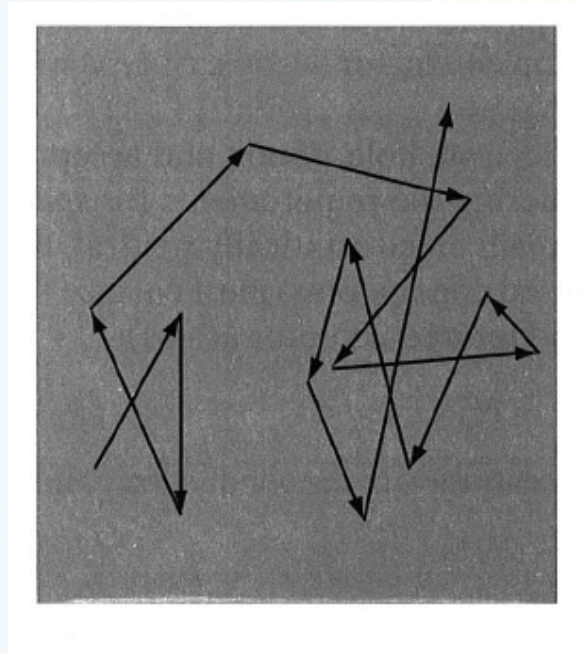


$$n_0 = p_0 = n_i$$



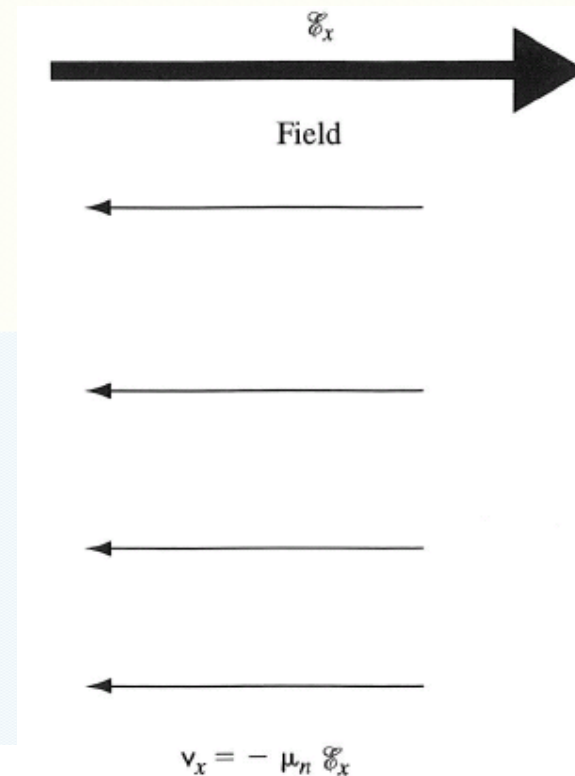
Conductivity and mobility

Thermal motion of the electron in the material.



On average, for a greater number of electrons, no net movement can be seen

Drift velocity in electric field



With an electric field, we get a net movement of electrons

Conductivity and mobility

$$\langle v_x \rangle = \frac{\langle p_x \rangle}{m_n^*} = -\frac{q\bar{t}}{m_n^*} \mathcal{E}_x$$

p_x and \bar{t} depends on the electrons scattering in the crystal lattice

\bar{t} is the average time between two scatterings

$$\frac{J_x}{\text{cm}^2} = \frac{J_x}{\text{ampere}} = \frac{\text{coulomb}}{\text{electron}} \cdot \frac{\text{electrons}}{\text{cm}^3} \cdot \frac{\text{cm}}{\text{s}}$$
$$J_x = -qn\langle v_x \rangle$$

$$J_x = \sigma \mathcal{E}_x, \quad \text{where } \sigma \equiv \frac{nq^2\bar{t}}{m_n^*}$$

$$\sigma = qn\mu_n, \quad \text{where } \mu_n \equiv \frac{q\bar{t}}{m_n^*}$$

mobility

Can also be written as

$$\mu_n = -\frac{\langle v_x \rangle}{\mathcal{E}_x}$$



Conductivity and mobility

Effective mass for conductivity is calculated for electrons in Silicon with;
Or can be downloaded from the table!

$$\frac{1}{m_n^*} = \frac{1}{3} \left(\frac{1}{m_l} + \frac{2}{m_t} \right)$$

Both holes and electrons!

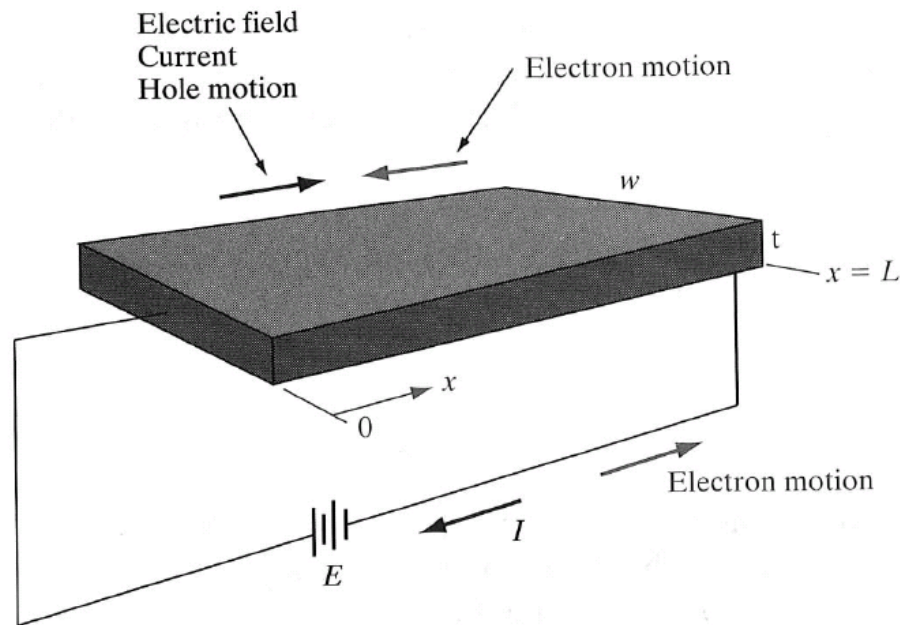
$$J_x = q(n\mu_n + p\mu_p)\mathcal{E}_x = \sigma\mathcal{E}_x$$

$$\mu_p = +\langle v_x \rangle / \mathcal{E}_x$$



Drift and Resistance

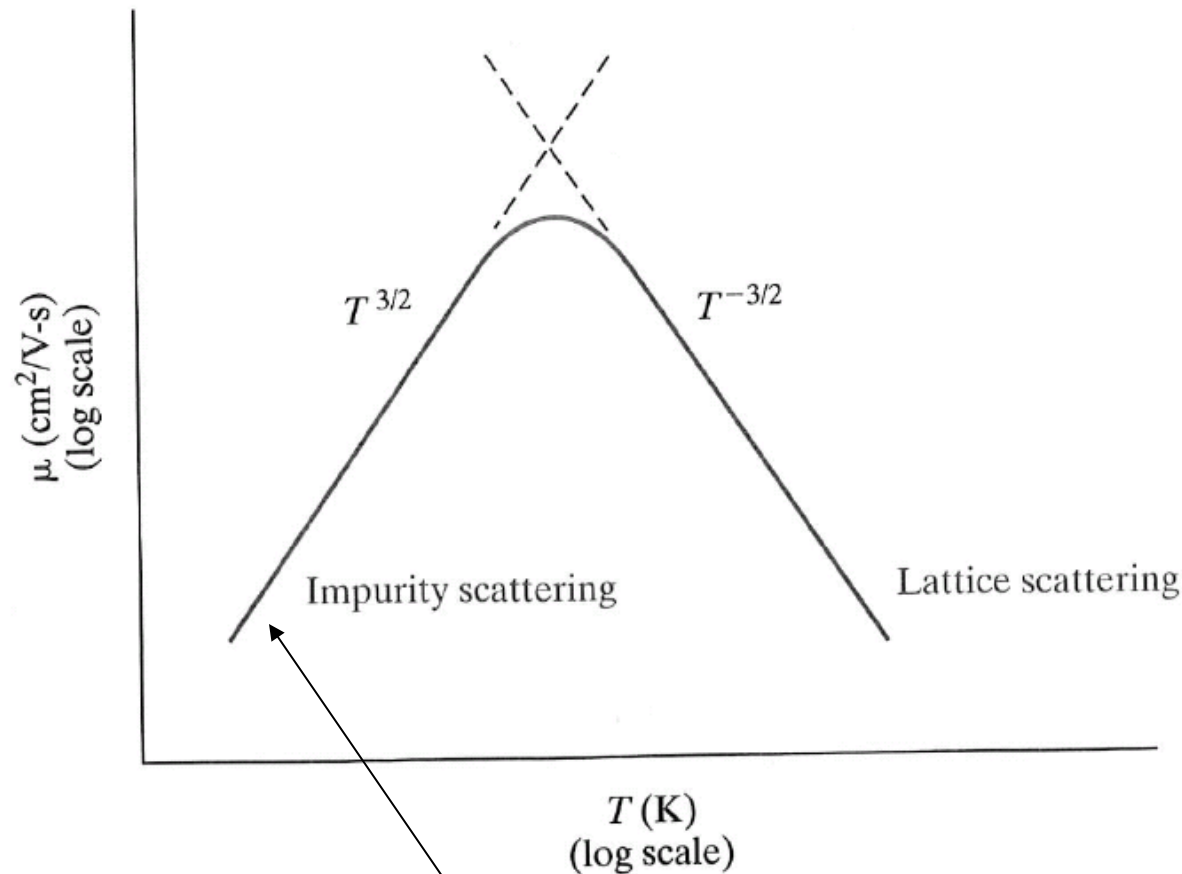
$$R = \frac{\rho L}{wt} = \frac{L}{wt} \frac{1}{\sigma}$$



Both hole and electron movement in the material.



Temperature and doping effects on mobility



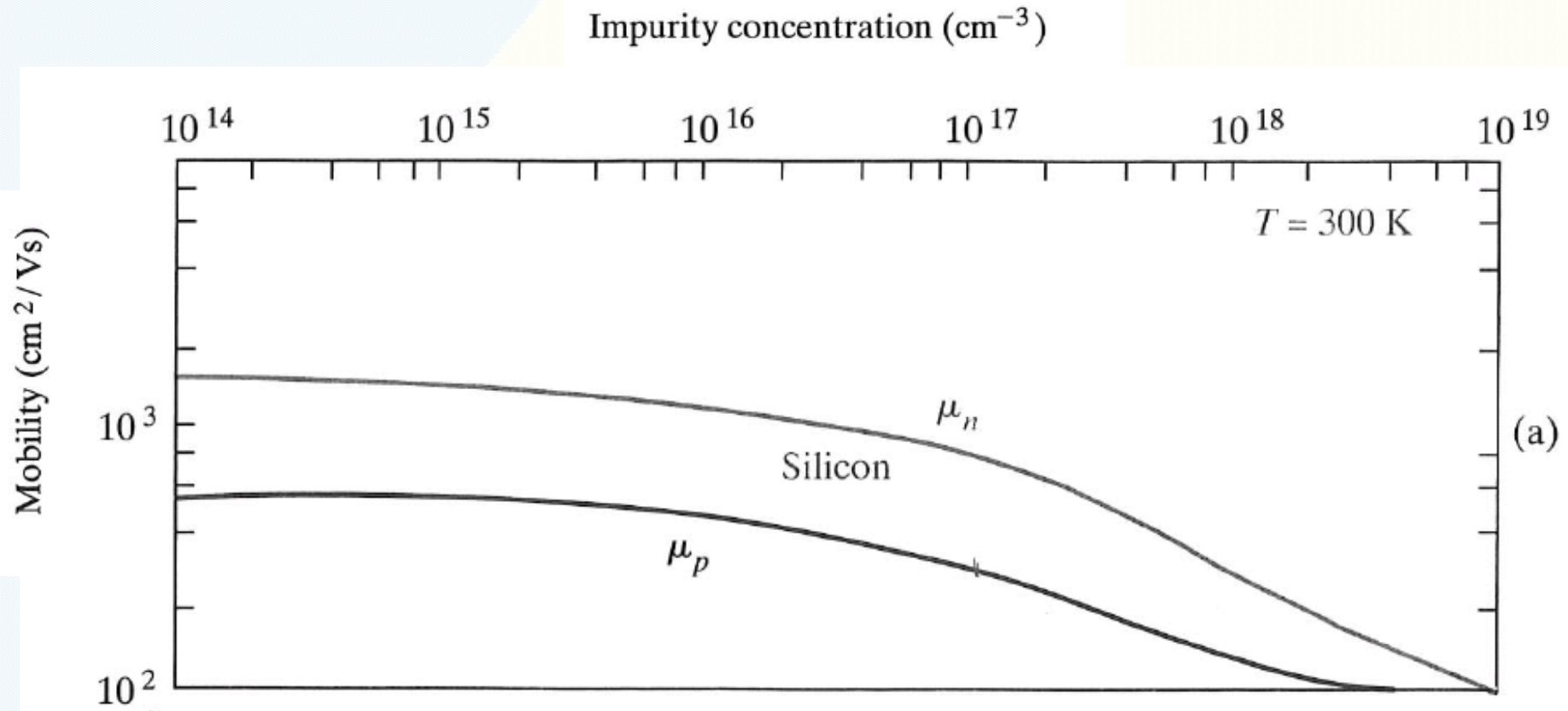
Calculation of mobility

$$\frac{1}{\mu} = \frac{1}{\mu_1} + \frac{1}{\mu_2} + \dots$$

The mechanism that causes the lowest mobility dominates!

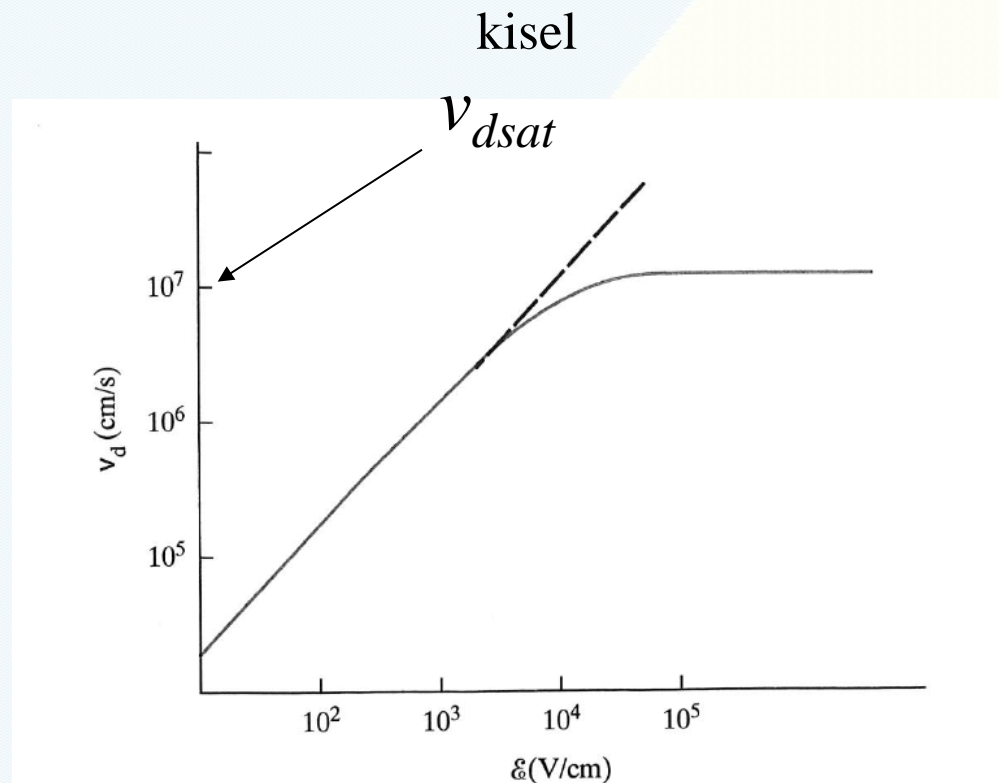
The probability increases for scattering when the thermal speed decreases for the charge carrier and the probability of scattering against ionized impurities (doping) increases

Temperature and doping effect on mobility



Effects at high field

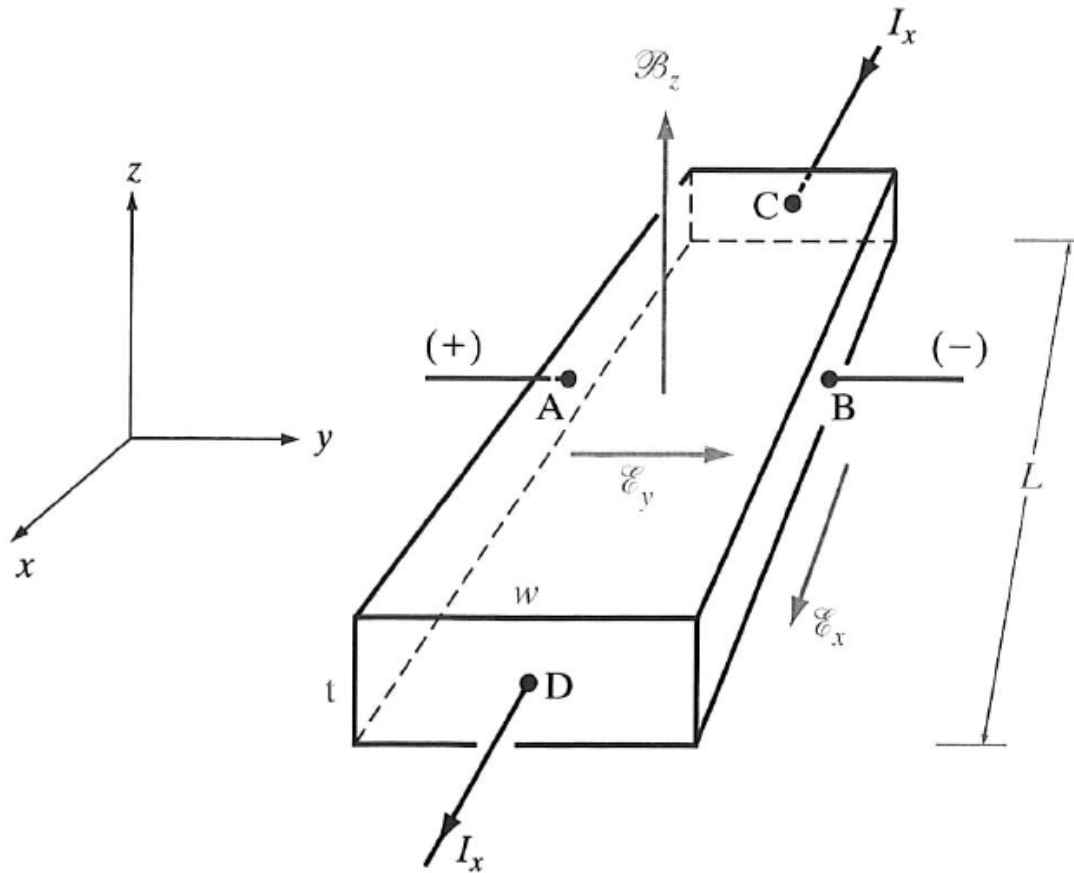
Charge carrier velocity has a maximum value!



$$\mu_n = - \frac{\langle v_x \rangle}{E_x}$$

At v_{dsat} reduces the mobility with increased electrical field

Hall effect (in a p-type semiconductor)



$$\mathbf{F} = q(\mathcal{E} + \mathbf{v} \times \mathcal{B})$$

$$F_y = q(\mathcal{E}_y - v_x \mathcal{B}_z)$$

Magnetic force acting on the holes

$$\mathcal{E}_y = v_x \mathcal{B}_z$$

An electric field arises that prevents further movement of holes

$$\mathcal{E}_y = \frac{J_x}{qp_0} \mathcal{B}_z = R_H J_x \mathcal{B}_z, \quad R_H \equiv \frac{1}{qp_0}$$

Hall coefficient



Hall effect (in a p-type semiconductor)

$$p_0 = \frac{1}{qR_H} = \frac{J_x \mathcal{B}_z}{q \mathcal{E}_y} = \frac{(I_x/wt) \mathcal{B}_z}{q(V_{AB}/w)} = \frac{I_x \mathcal{B}_z}{qtV_{AB}}$$

Measurement of Hall voltage gives an accurate measurement of hole concentration

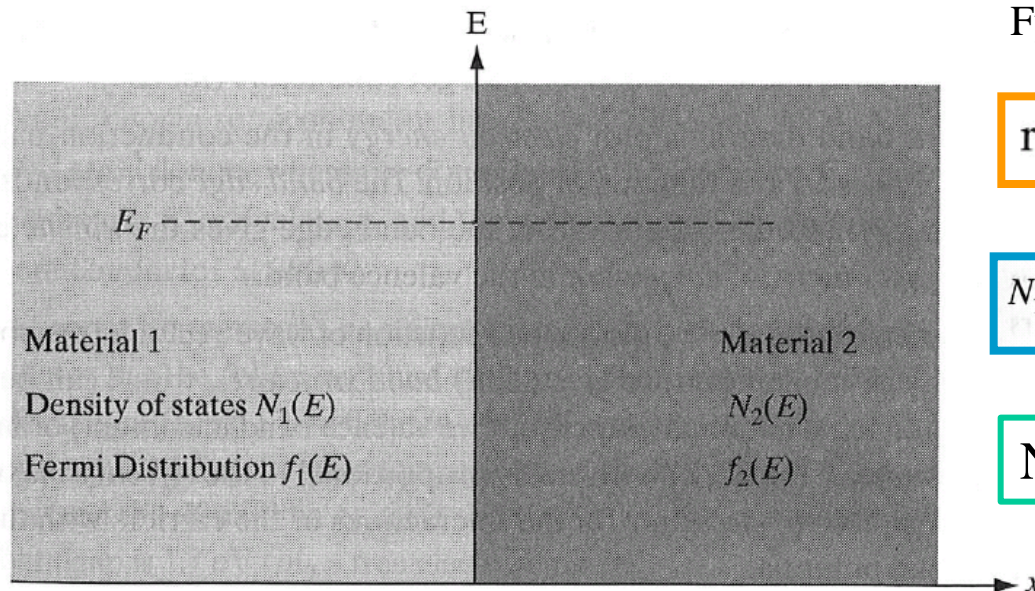
$$\rho(\Omega\text{-cm}) = \frac{Rwt}{L} = \frac{V_{CD}/I_x}{L/wt}$$

$$\mu_p = \frac{\sigma}{qp_0} = \frac{1/\rho}{q(1/qR_H)} = \frac{R_H}{\rho}$$

Hall coefficient and resistivity produces a measurement of mobility



Fermi level at equilibrium



$$\text{rate from 1 to 2} \propto N_1(E)f_1(E) \cdot N_2(E)[1 - f_2(E)]$$

Fyllda tillstånd i M1

Ofyllda tillstånd i M2

$$\text{rate from 2 to 1} \propto N_2(E)f_2(E) \cdot N_1(E)[1 - f_1(E)]$$

$$N_1(E)f_1(E) \cdot N_2(E)[1 - f_2(E)] = N_2(E)f_2(E) \cdot N_1(E)[1 - f_1(E)]$$

$$N_1 f_1 N_2 - N_1 f_1 N_2 f_2 = N_2 f_2 N_1 - N_2 f_2 N_1 f_1$$

$$f_1(E) = f_2(E), \quad \text{that is, } [1 + e^{(E - E_{F1})/kT}]^{-1} = [1 + e^{(E - E_{F2})/kT}]^{-1}$$

$$E_{F1} = E_{F2}$$

